

TSMC-01-1510

February 27, 2004

To: Commissioner for Patents  
P.O.Box 1450  
Alexandria, VA 22313-1450

Fr: George O. Saile, Reg. No. 19,572  
28 Davis Avenue  
Poughkeepsie, N.Y. 12603

Subject: | Serial No. 10/749,698 12/31/03 |  
Cheng I. Sun et al.  
MULTIVARIATE RBR TOOL AGING ADJUSTER  
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#### INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation  
In An Application.

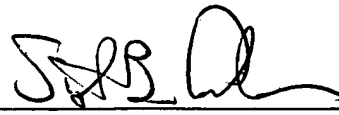
The following Patents and/or Publications are submitted to  
comply with the duty of disclosure under CFR 1.97-1.99 and  
37 CFR 1.56.

#### CERTIFICATE OF MAILING

I hereby certify that this correspondence is being  
deposited with the United States Postal Service as first class  
mail in an envelope addressed to: Commissioner for Patents,  
P.O. Box 1450, Alexandria, VA 22313-1450, on March 1, 2004.

Stephen B. Ackerman, Reg.# 37761

Signature/Date

 3/1/04

U.S. Patent 5,963,902 to Wang, "Methods and Apparatus for Decreasing the Size of Generated Models Trained for Automatic Pattern Recognition," discusses using an expectation maximization (EM) model in a pattern recognition process.

U.S. Patent 6,238,936 to Yu, "Method of Using Critical Dimension Mapping to Qualify a New Integrated Circuit Fabrication Etch Process," teaches mapping critical dimension (CD) of predetermined features at various process stages.

U.S. Patent 5,757,673 to Osheiski et al., "Automated Data Management System for Analysis and Control of Photolithography Stepper Performance," teaches automated analysis of data from self-tests of steppers uploaded as an ASCII file.

U.S. Patent 6,245,581 to Bonser et al., "Method and Apparatus for Control of Critical Dimension Using Feedback Etch Control," teaches a method of measuring critical dimension, analyzing the measurement, and performing a secondary etch process based on the analysis.

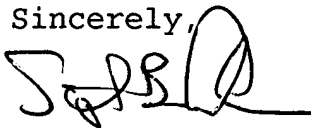
U.S. Patent 5,862,054 to Li, "Process Monitoring System for Real Time Statistical Process Control," discloses a process parameter monitoring system.

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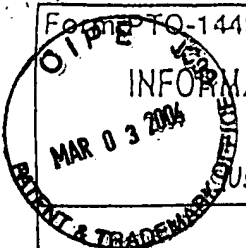
U.S. Patent 6,263,255 to Tan et al., "Advanced Process Control for Semiconductor Manufacturing," discloses a software framework for measurement, processing, and strategy control of a factory.

U.S. Patent 5,243,377 to Umatate et al., "Lithography Information Control System," discloses a lithography control system.

U.S. Patent Application TSMC-01-1509, Serial #10/313,501, filed 12/6/02, assigned to the same assignees, "Multivariate RBR Tool Aging Detector," discusses fabrication of integrated circuit devices.

Sincerely,  


Stephen B. Ackerman,  
Reg. No. 37761



Form PTO-1449		Doc No (Number) (Specimen)	Application Number
INFORMATION DISCLOSURE CITATION IN AN APPLICATION		TSMC-01-1510	10/749,698
Use several sheets if necessary		Applicant: Cheng I. Sun et al.	
		Filing Date: 12/31/03	Group Art. Unit

U. S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	ALWD DATE & APPROXIMATE
	5963902	10/5/99	Wang	704	243	7/30/97
	6238936	5/29/01	Yu	438	7	3/8/99
	5757673	5/26/98	Osheiski et al.	364	552	10/10/96
	6245581	6/12/01	Bonser et al.	438	8	4/19/00
	5862054	1/19/99	Li	364	468.28	2/20/97
	6263255	7/17/01	Tam et al.	700	121	5/18/98
	5243377	9/7/93	Umatate et al.	355	53	3/31/92

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Portion of Pages, Etc.)

-	U.S. Patent Application TSMC-01-1509, Ser # 10/313,501, filed 12/6/02, assigned to the same assignees, "Multivariate RBR Tool Aging Detector."

EXAMINER	DATE CONSIDERED
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EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.